

Title (en)

METHOD FOR PRODUCING A MICROMECHANICAL COMPONENT HAVING A TRENCH STRUCTURE FOR BACKSIDE CONTACT

Title (de)

VERFAHREN ZUR HERSTELLUNG EINES MIKROMECHANISCHEN BAUELEMENTS MIT TRENCHSTRUKTUR ZUR RÜCKSEITENKONTAKTIERUNG

Title (fr)

PROCÉDÉ DE FABRICATION D'UN COMPOSANT MICROMÉCANIQUE COMPORTANT UNE STRUCTURE DE TRANCHÉE DE MISE EN CONTACT SUR LA FACE ARRIÈRE

Publication

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Application

EP 08735959 A 20080408

Priority

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Abstract (en)

[origin: WO2008132028A2] The invention relates to a method for producing a micromechanical component. The aim of the invention is to produce at least one trench structure in a substrate, said trench structure having a depth that is less than the substrate thickness. An insulating layer is applied to a first face of the substrate and a filler layer is produced on or applied to the substrate. Said filler layer comprises a filler material that fills the trench structure essentially completely. A planarization within a plane of the filler layer or the insulating layer or the substrate produces a planar first face of the substrate. Subsequently, the second face of the substrate is planarized. The invention also relates to a micromechanical component which is produced according to said method.

IPC 8 full level

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US 2002167072 A1 20021114 - ANDOSCA ROBERT GEORGE [US]

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